INFORMATION	DISCLOSURE

CITATION (Use several sheets if necessary)

Atty. Docket No.	Serial No.
4662-138	10/565,505

4662-138 Applicant

SHAHAB et al

TC/A.U. July 6, 2006 1795

				U.S. PATENT DOCUMENTS				
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*Examiner		Date Considered	
	eference considered, whether or not citation is in conformance with M h next communication to applicant.	MPEP 609; Draw line through cita	ion if not in conformance and not considered. Include